

In the Claims:

Please amend the claims as follows. A complete listing of the claims proper claim identifiers is set forth below.

1. (Currently Amended) A run-to-run method for the computer-aided monitoring and controlling of a manufacturing process of a plurality of wafers, the method comprising the step of:

~~in which the wafers are subjected~~ a plurality of wafers to at least one manufacturing step;

~~in which at least one of the processed wafers is~~ mark at least one of the processed wafers ~~marked~~ according to a deterministic selection criterion in such a way that it can be subjected to an inline SPC measurement;

~~in which the manufacturing process is controlled~~ controlling the manufacturing process on the basis of the result of the inline SPC measurement of the wafer[[],]; and

~~in which at least one wafer necessary for the run-to-run method and also for the inline SPC method is selected~~ selecting at least one wafer necessary for the run-to-run method and also for the inline SPC method according to the deterministic selection criterion.

2. (Original) The method as claimed in claim 1, in which the deterministic selection criterion is determined by means of rules.

3. (Currently Amended) A device for the monitoring and controlling of a manufacturing process of a plurality of wafers, with a processor which is set up to run ~~in such a way that the following method steps of a run-to-run method, the device comprising, can be carried out:~~

an element for carrying out at least one manufacturing step on the wafers;

an element for marking at least one of the wafers according to a deterministic selection criterion in such a way that it can be subjected to an inline SPC measurement, at least one wafer necessary for the run-to-run method and also for the

inline SPC method being selected according to the deterministic selection criterion;
and

an element for controlling the manufacturing process on the basis of the
result of the inline SPC measurement.

4. (Currently Amended) A computer-readable storage medium, in which
a program for the monitoring and controlling of a manufacturing process of a plurality
of wafers is stored, the monitoring and controlling being carried out by means of a
run-to-run method, which program executes the following method steps when it is run
by a processor, the computer-readable storage medium comprising:

a code carrying out at least one manufacturing step on the wafers;
marking at least one of the processed wafers according to a
deterministic selection criterion in such a way that it can be subjected to an inline SPC
measurement, at least one wafer necessary for the run-to-run method and also for the
inline SPC method being selected according to the deterministic selection criterion;
and

controlling the manufacturing process on the basis of the result of the
inline SPC measurement.

5. (Currently Amended) A program element for the monitoring and
controlling of a manufacturing process of a plurality of wafers, the monitoring and
controlling being carried out by means of a run-to-run method, which element
executes the following method steps when it is run by a processor, the program
element comprising:

code for carrying out at least one manufacturing step on the wafers;
code for marking at least one of the processed wafers according to a
deterministic selection criterion in such a way that it can be subjected to an inline SPC
measurement, at least one wafer necessary for the run-to-run method and also for the
inline SPC method being selected according to the deterministic selection criterion;
and

code for controlling the manufacturing process on the basis of the result
of the inline SPC measurement.